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(54) Title: ISOLATION OF NOVOLAK RESIN WITHOUT HIGH TEMPERATURE DISTILLATION AND PHOTORESIST COMPOSITION THEREFROM (57) Abstract The present invention provides a method for producing a water insoluble, aqueous alkali soluble novolak resins fractions having consistent molecular weight and superior performance in photoresist composition, by fractionating novolak resins according to molecular weight. A method is also provided for producing photoresist composition from such a novolak resin and for producing semiconductor devices using such a photoresist composition.		